

## Supporting Information

### **A surface oxide layer of copper nanowires enhanced the UV selective response of a ZnO film photodetector**

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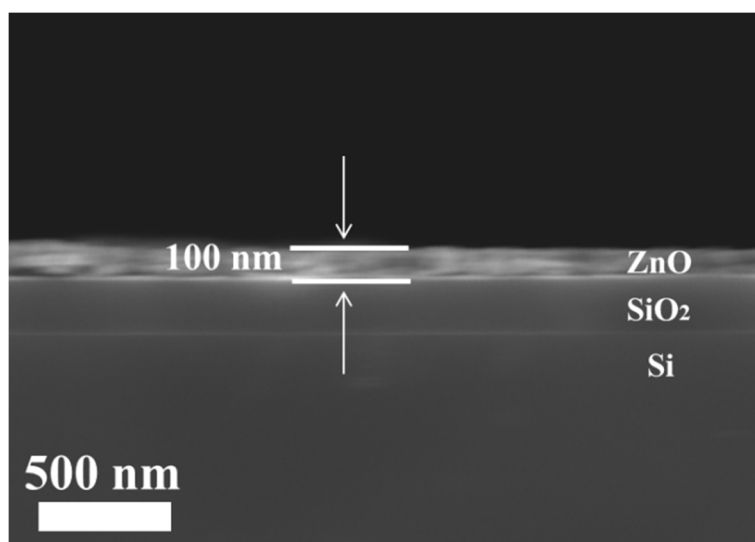


Fig. S1. The cross-section image of ZnO film prepared by spin-coating method.

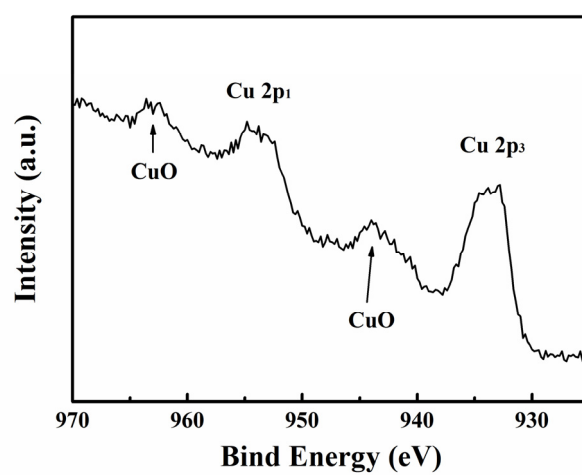


Fig. S2. The Cu 2p XPS spectra.

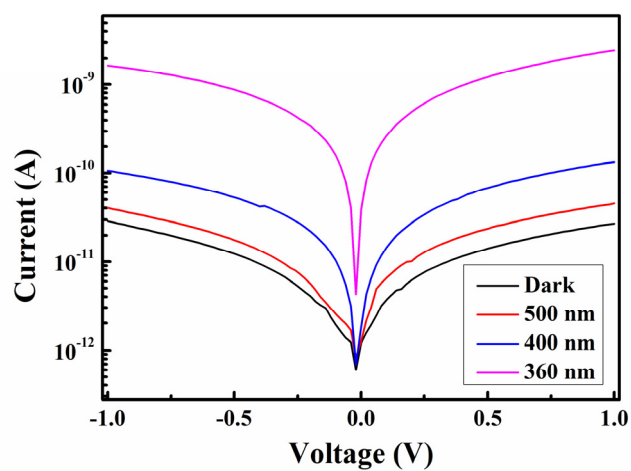


Fig. S3. The semi-log I-V curves of the Cu NW/ZnO PD in dark and under 360, 400 and 500 nm light illumination.

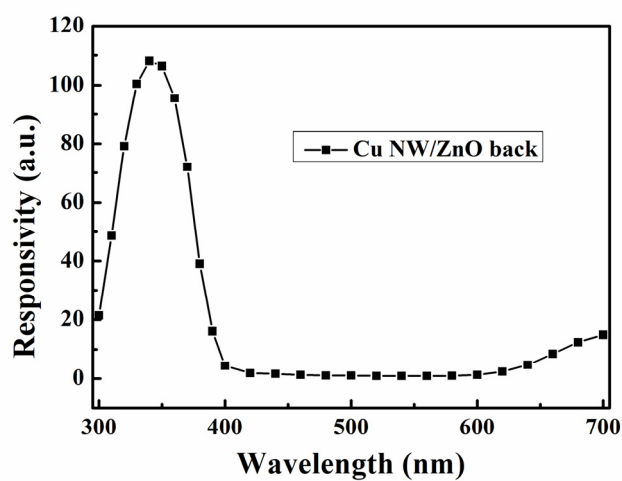


Fig. S4. The photo responsivity spectra of the Cu NW/ZnO composite with the UV light illuminated from the back side.

Table S1. Summary of the optoelectronic performance of the MSM type photodetector based on ZnO films.

| MSM type PDs based on ZnO films | Preparation method        | Contact type      | Bias voltage | Responsivity at UV region | Rejecti on ratio | Ref.      |
|---------------------------------|---------------------------|-------------------|--------------|---------------------------|------------------|-----------|
| Au/ZnO film/Au                  | Molecular-beam epitaxy    | Schottky/Schottky | 0 V          | 20 mA/W                   | 100              | 1         |
| Au/ZnO film/In                  | RF magnetron sputtering   | Schottky/Ohmic    | 5 V          | 0.36 mA/W                 | 10 <sup>4</sup>  | 2         |
| Au/ZnO rods/Au                  | Hydrothermal              | Schottky/Schottky | 1 V          | 1.44×10 <sup>5</sup> A/W  | 17.4             | 3         |
| Au/Density ZnO rods/Au          |                           |                   | 1 V          | 7.01×10 <sup>3</sup> A/W  | 281.2            |           |
| Au/ZnO:Ga/Au                    | Aqueous solution method   | Schottky/Schottky | 1 V          | 5.75 A/W                  | 36.1             | 4         |
| Au/ZnO wall/Au                  | Thermal evaporation       | Schottky/Schottky | 5 V          | ~ 4 A/W                   | 29               | 5         |
| AuAg/ZnO rods/AuAg              | Hydrothermal              | Schottky/Schottky | 1 V          | 10 <sup>2</sup> A/W       | 174.6            | 6         |
| Au/ZnONW & Graphene/Au          | CVD Hydrothermal          | Schottky/Schottky | 1 V          | 188 A/W                   | 10 <sup>4</sup>  | 7         |
| Au/ZnONW/Au                     | Hydrothermal              | Schottky/Schottky | 1 V          |                           | 10-100           |           |
| Au/PEDOT:PSS/ZnO/TiAu           | Single crystal ZnO        | Schottky/Ohmic    | 0 V          | 0.3 A/W                   | 10 <sup>3</sup>  | 8         |
| CrAu/ZnO/CrAu                   | Spin-coating              | Ohmic/Ohmic       | 1 V          | 0.9 mA/W                  | 3.7              | This work |
| Ag/Cu/ZnO/Ag                    | Spin-coating              | Schottky/Ohmic    | 1 V          | 1.1 mA/W                  | 67               |           |
| Ag/CuNW/ZnO/Ag                  | Hydrothermal Spin-coating | Schottky/Ohmic    | 1 V          | 0.65 mA/W                 | 160              |           |

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